

Supporting Information

Nitrogen and Sulfur Co-Doped $Ti_3C_2T_x$ MXene for High-Rate Lithium-Ion Batteries

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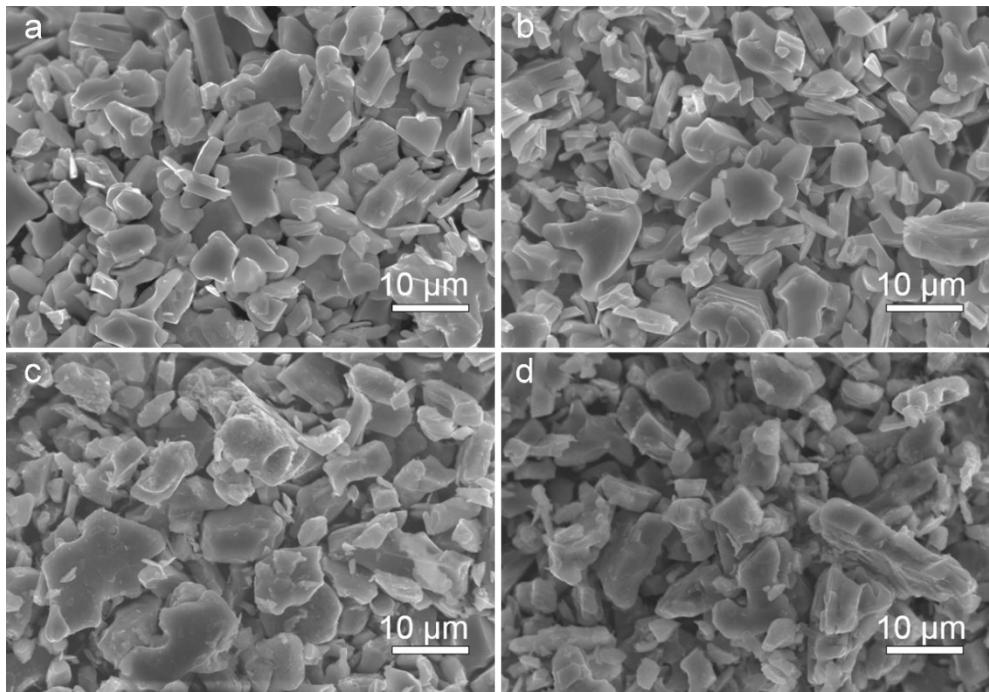


Fig. S1 SEM images of (a) $\text{Ti}_3\text{C}_2\text{T}_x$, (b) $\text{N}-\text{Ti}_3\text{C}_2\text{T}_x$, (c) $\text{NS}_{0.1}-\text{Ti}_3\text{C}_2\text{T}_x$, and (d) $\text{NS}_{0.5}-\text{Ti}_3\text{C}_2\text{T}_x$.

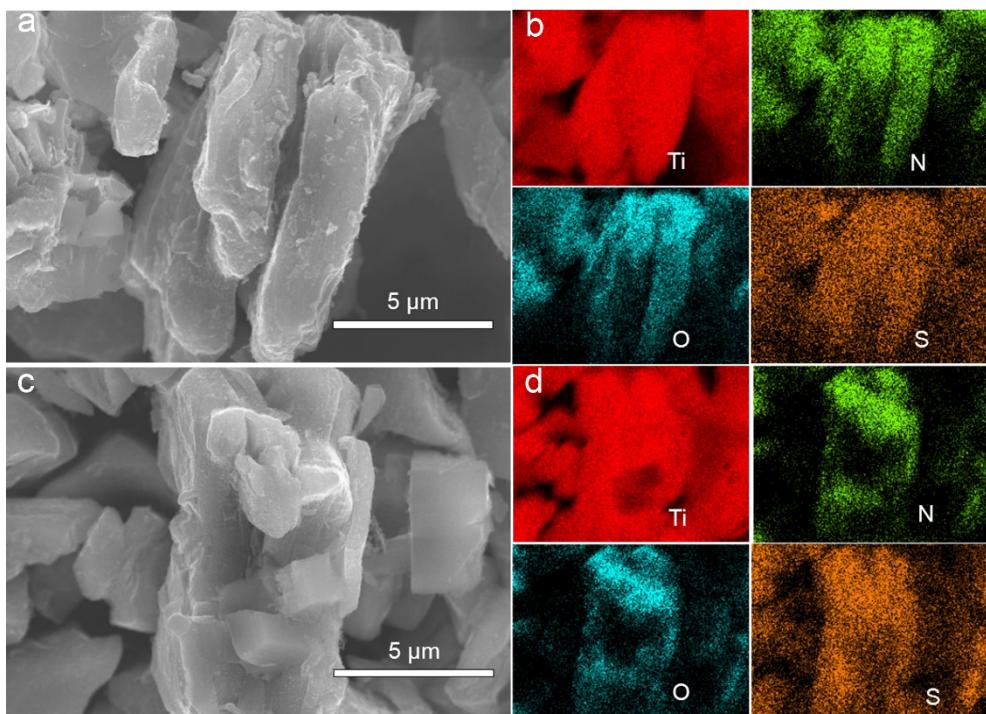


Fig. S2 (a) $\text{NS}_{0.1}-\text{Ti}_3\text{C}_2\text{T}_x$, corresponding elemental mapping images (b) for the distribution of Ti, N, O and S elements, respectively. (c) $\text{NS}_{0.5}-\text{Ti}_3\text{C}_2\text{T}_x$, corresponding elemental mapping images (d) for the distribution of Ti, C, O and S elements, respectively.

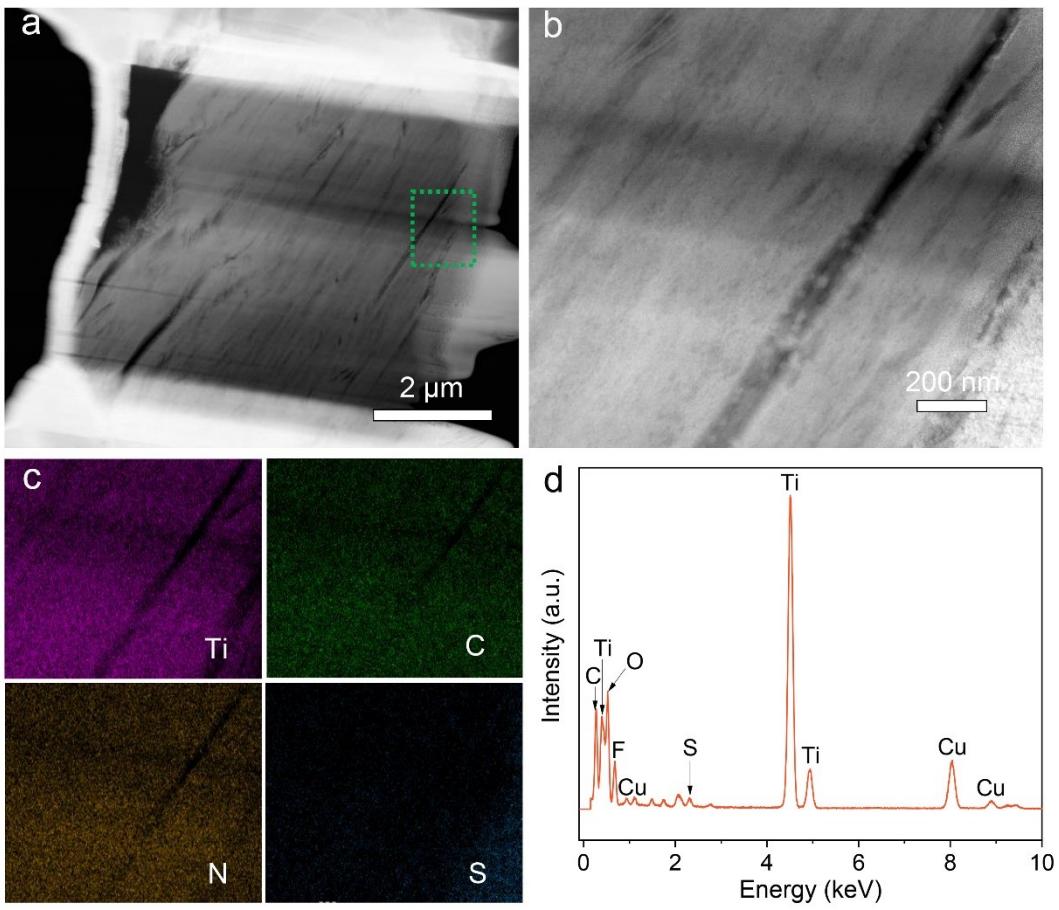


Fig. S3 Typical STEM image and EDS mapping of $\text{NS}_{0.3}\text{-Ti}_3\text{C}_2\text{T}_x$. (a) Cross sectional microstructure of $\text{NS}_{0.3}\text{-Ti}_3\text{C}_2\text{T}_x$. (b) HAADF image of marked area by green rectangular and (c) corresponding elemental mappings of Ti, C, N, and S elements. (d) STEM-EDS spectrum of $\text{NS}_{0.3}\text{-Ti}_3\text{C}_2\text{T}_x$. The atomic ratios of elements are listed in Table S1.

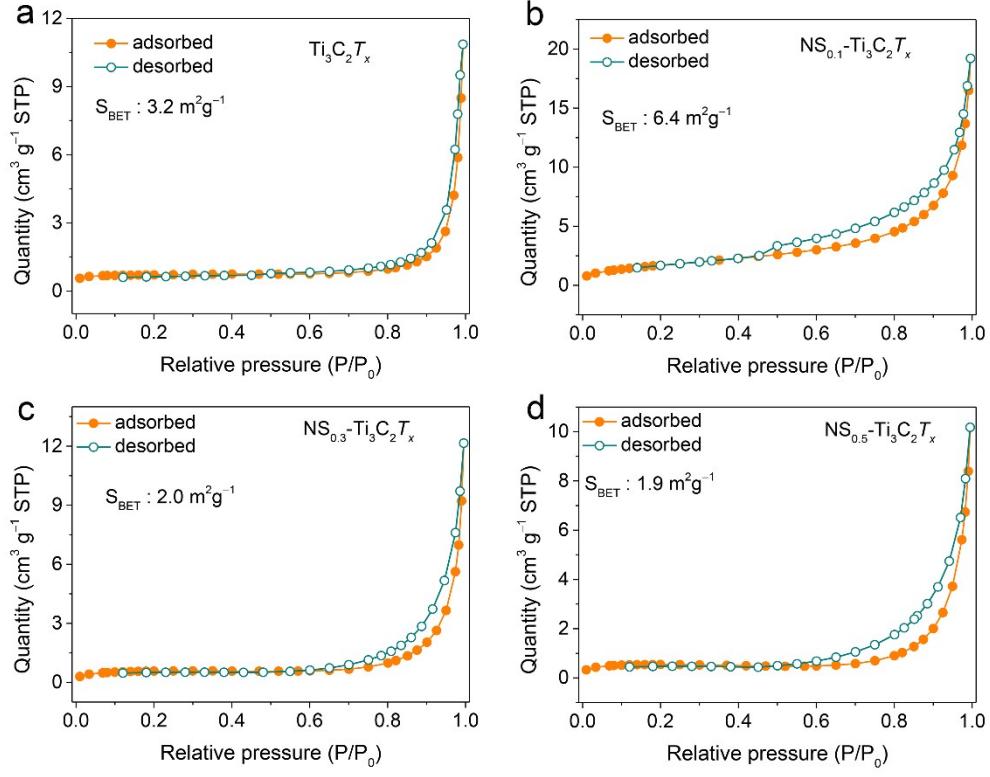


Fig. S4 Nitrogen adsorption/desorption isotherms of (a) pristine $Ti_3C_2T_x$, (b) $NS_{0.1}-Ti_3C_2T_x$, (c) $NS_{0.3}-Ti_3C_2T_x$ and (d) $NS_{0.5}-Ti_3C_2T_x$. The BET specific surface areas of aforementioned samples are 3.2 , 6.4 , 2.0 and $1.9 \text{ m}^2 \text{g}^{-1}$, respectively.

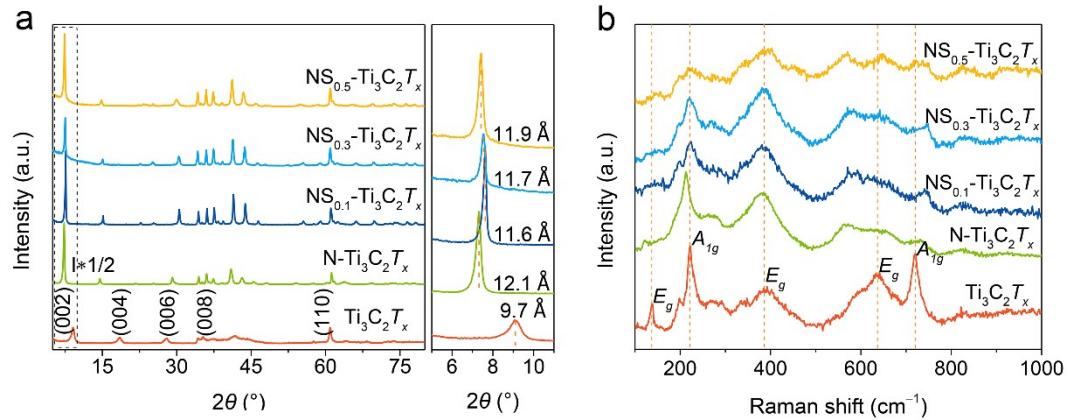


Fig. S5 (a) XRD patterns and (b) Raman spectra of pristine $Ti_3C_2T_x$ and N, S co-doped $Ti_3C_2T_x$.

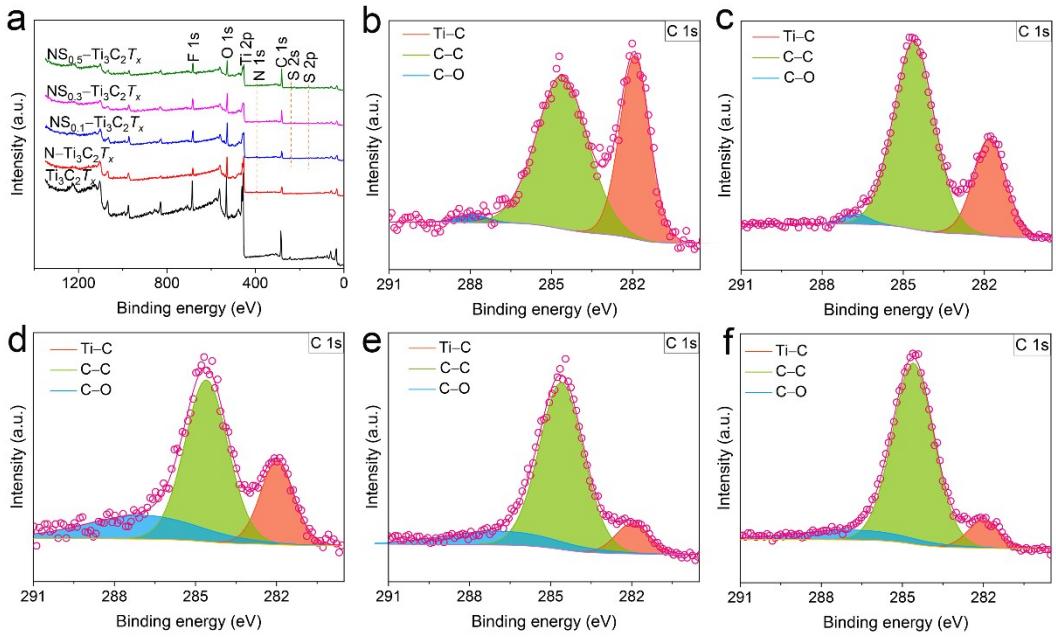


Fig. S6 (a) XPS survey spectra of pristine $\text{Ti}_3\text{C}_2\text{T}_x$, N- $\text{Ti}_3\text{C}_2\text{T}_x$, NS_{0.1}- $\text{Ti}_3\text{C}_2\text{T}_x$, NS_{0.3}- $\text{Ti}_3\text{C}_2\text{T}_x$, and NS_{0.5}- $\text{Ti}_3\text{C}_2\text{T}_x$. High-resolution C 1s XPS spectra of (b) $\text{Ti}_3\text{C}_2\text{T}_x$, (c) N- $\text{Ti}_3\text{C}_2\text{T}_x$, (d) NS_{0.1}- $\text{Ti}_3\text{C}_2\text{T}_x$, (e) NS_{0.3}- $\text{Ti}_3\text{C}_2\text{T}_x$, and (f) NS_{0.5}- $\text{Ti}_3\text{C}_2\text{T}_x$. The XPS spectra were recorded after Ar sputtering for 120 s.

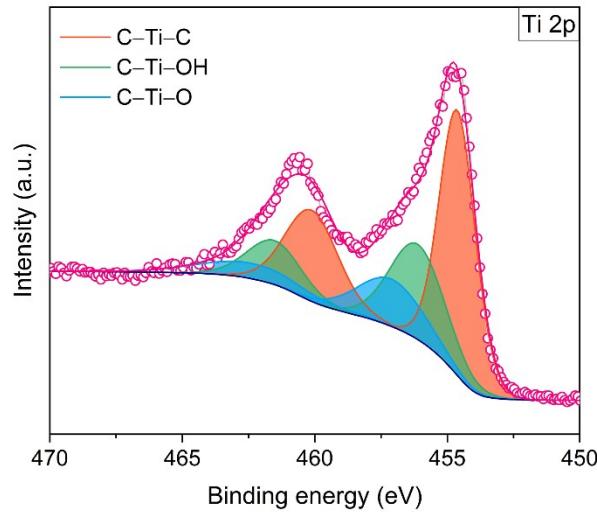


Fig. S7 High-resolution Ti 2p XPS spectra of pristine $\text{Ti}_3\text{C}_2\text{T}_x$. The XPS spectra were recorded after Ar sputtering for 120 s.

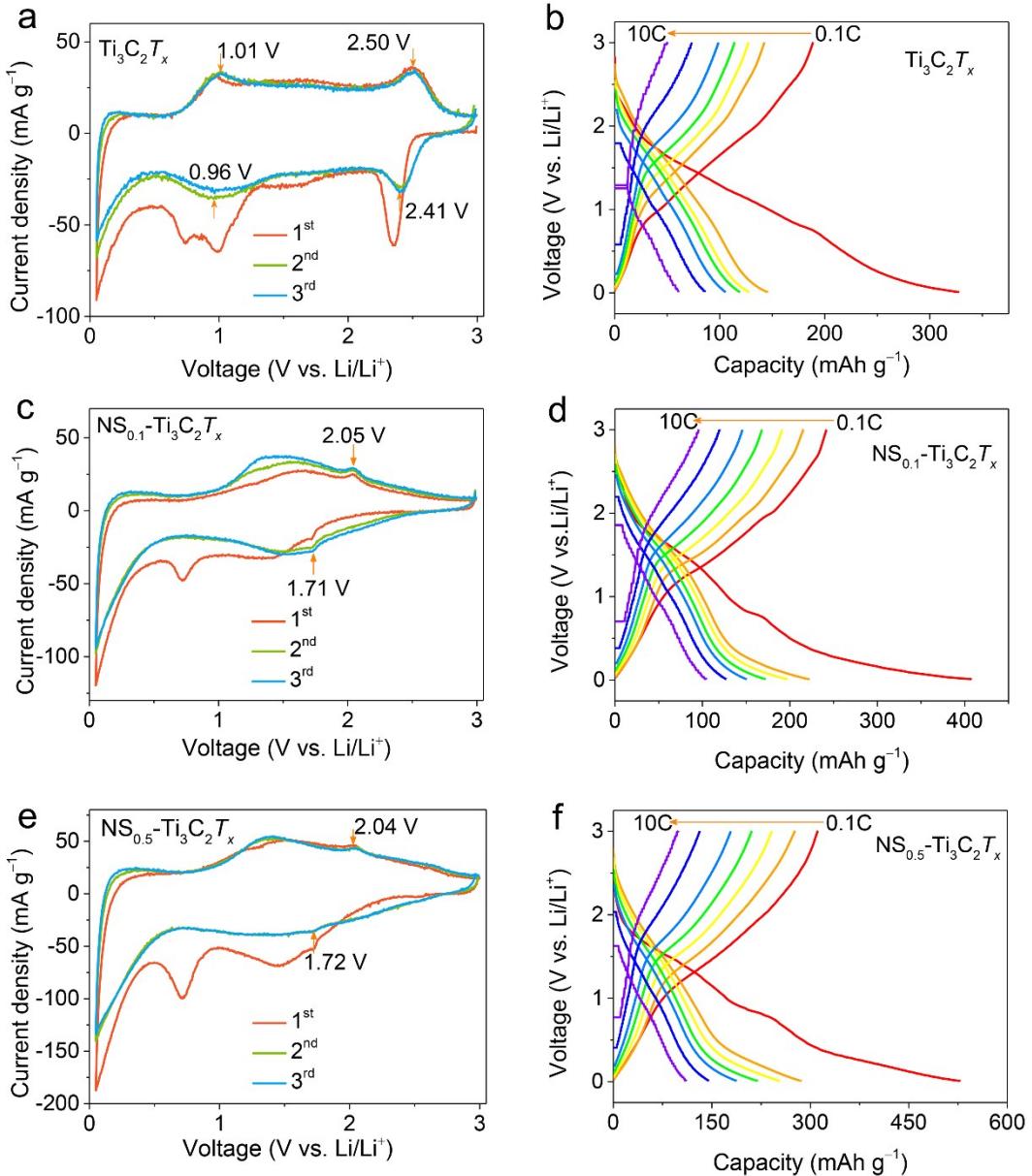


Fig. S8 CV curves of (a) pristine $\text{Ti}_3\text{C}_2\text{T}_x$, (c) $\text{NS}_{0.1}\text{-Ti}_3\text{C}_2\text{T}_x$, (e) $\text{NS}_{0.5}\text{-Ti}_3\text{C}_2\text{T}_x$ electrodes. Galvanostatic charge and discharge curves of (b) $\text{N-Ti}_3\text{C}_2\text{T}_x$, (d) $\text{NS}_{0.1}\text{-Ti}_3\text{C}_2\text{T}_x$ and (f) $\text{NS}_{0.5}\text{-Ti}_3\text{C}_2\text{T}_x$ cycled at various rates.

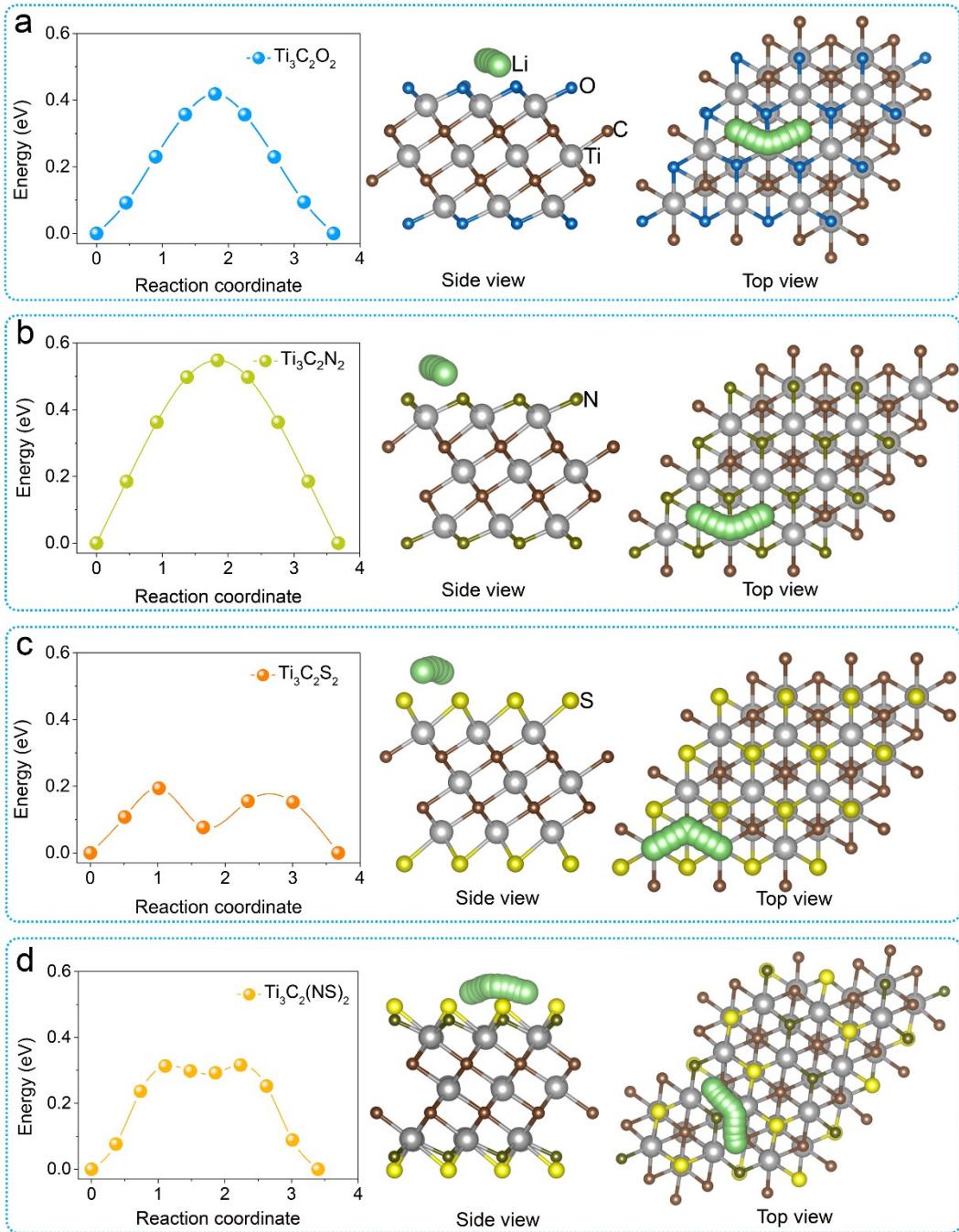


Fig. S9 Diffusion barrier profiles of Li on (a) $\text{Ti}_3\text{C}_2\text{O}_2$, (b) $\text{Ti}_3\text{C}_2\text{N}_2$, (c) $\text{Ti}_3\text{C}_2\text{S}_2$ and (d) $\text{Ti}_3\text{C}_2(\text{NS})_2$ and the corresponding energetically optimized Li migration pathways from side and top view.

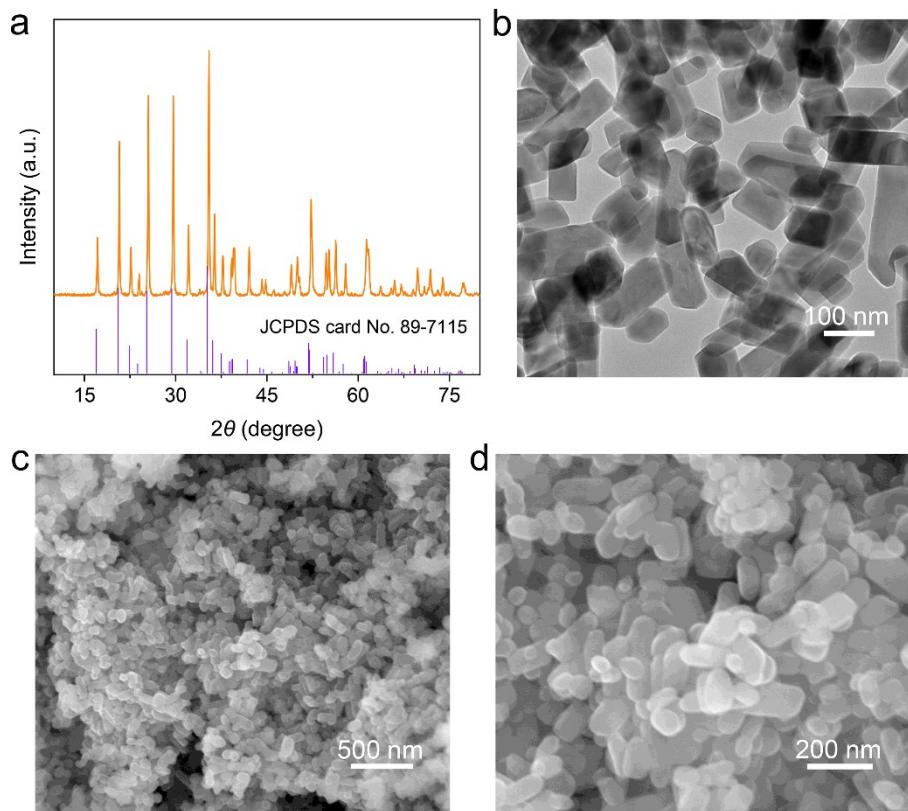


Fig. S10 XRD pattern of the as-prepared $\text{LiMn}_{0.5}\text{Fe}_{0.5}\text{PO}_4$ product. TEM image (b), and SEM images (c, d) of $\text{LiMn}_{0.5}\text{Fe}_{0.5}\text{PO}_4/\text{C}$ material.

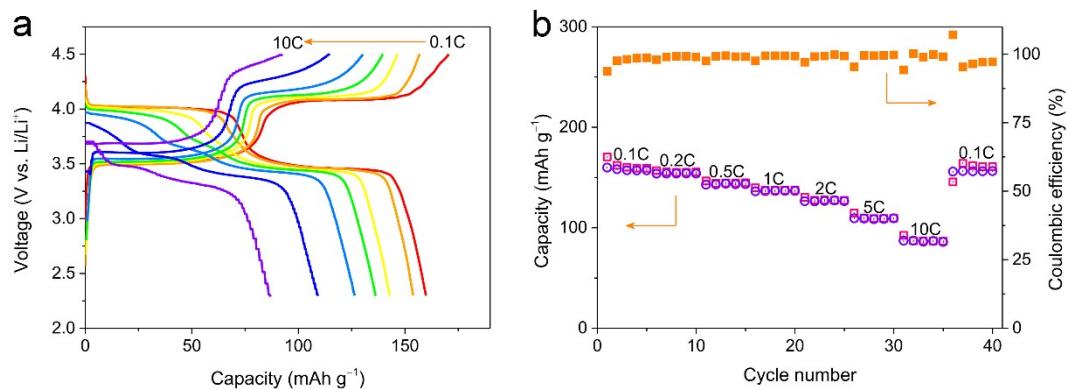


Fig. S11 (a) Typical charge/discharge curves of $\text{LiMn}_{0.5}\text{Fe}_{0.5}\text{PO}_4/\text{C}$ at current rates ranging from 0.1 to 10C. (b) Rate capability.

Table S1 Summary of atomic ratio in the NS_{0.3}–Ti₃C₂T_x.

x	Element							
	C	O	F	Al	Si	S	Ti	Cu
Subsurface	25.22	13.59	5.02	0.68	0.35	1.11	45.36	8.67
Interior	20.58	11.99	5.16	0.56	0.42	0.70	51.27	9.31

Table S2 Atomic concentration of elements in surface layers of pristine–Ti₃C₂T_x, N–Ti₃C₂T_x, NS_{0.1}–Ti₃C₂T_x, NS_{0.3}–Ti₃C₂T_x, and NS_{0.5}–Ti₃C₂T_x, samples.

Sample	Element						
	Ti	O	C	F	Al	N	S
pristine–Ti ₃ C ₂ T _x	19.0	21.3	36.0	14.4	9.3	-	-
N–Ti ₃ C ₂ T _x	27.2	25.1	32.1	7.4	5.2	3.0	-
NS _{0.1} –Ti ₃ C ₂ T _x	10.9	17.4	52.6	8.2	6.9	2.5	1.5
NS _{0.3} –Ti ₃ C ₂ T _x	12.0	16.7	55.3	7.8	3.4	2.0	2.9
NS _{0.5} –Ti ₃ C ₂ T _x	11.1	15.3	54.2	9.6	3.5	3.5	2.8

Table S3 Ti 2p core level peak analyses of Ti₃C₂T_x MXenes after Ar⁺ sputtering 120 s. The Ti 2p core level was fitted with a fixed area ratio of 2:1 for all Ti 2p_{3/2}–Ti2p_{1/2} and doublet separation of 5.5 eV for C–Ti–C, C–Ti–OH, C–Ti–O, C–Ti–S, C–Ti–N, and C–Ti–ON.

Sample	Fraction / %					
	C–Ti–C	C–Ti–N	C–Ti–OH	C–Ti–S	C–Ti–O	C–Ti–ON
	454.9±0.1eV	455.5±0.1eV	456.3±0.1eV	457.0±0.1eV	457.2eV±0.1eV	458.2±0.1eV
pristine–Ti ₃ C ₂ T _x	–	–	28.6	–	–	–
^x	53.6	–	–	–	17.8	–
N–Ti ₃ C ₂ T _x	40	5.0	–	–	50	5.0
NS _{0.1} –Ti ₃ C ₂ T _x	42.3	6.3	–	4.2	40.9	6.3
NS _{0.3} –Ti ₃ C ₂ T _x	41.5	1.2	–	5.0	49.8	2.5
NS _{0.5} –Ti ₃ C ₂ T _x	45.2	3.1	–	6.2	42.4	3.1

Table S4. Comparison of the volume expansion for $\text{NS}_{0.3}\text{-Ti}_3\text{C}_2T_x$ in our work with widely reported electrode materials.

Samples	Volume expansion (%)	Reference
$\text{NS}_{0.3}\text{-Ti}_3\text{C}_2T_x$	0.6	This work
LiCoO_2	1.8	Ref. ¹
VPO_4	2.1	Ref. ²
NCM111	1.2	Ref. ³
Nb_2CT_x	2.3	Ref. ⁴
LiFePO_4	6.8	Ref. ⁵
VO_2	6.0	Ref. ⁶
LiMn_2O_4	16	Ref. ⁷
$\text{Li}_4\text{Ti}_5\text{O}_{12}$	0.8	Ref. ⁸
Graphite	10.7	Ref. ⁹
TiO_2	3.7	Ref. ¹⁰

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